

Hydrosilylation of Cyclohexene, 1-Methylcyclohexene, and Isopropylidenecyclohexane

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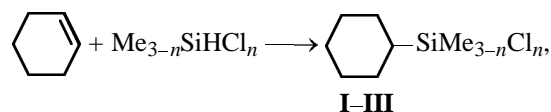
Abstract—Hydrosilylation of cyclohexene and isopropylidenecyclohexane with chloro(methyl)silanes $\text{Me}_{3-n}\text{SiHCl}_n$ ($n = 1-3$) gives rise to cyclohexyl- and chloro(2-cyclohexylpropyl)methylsilanes. Hydrosilylation of 1-methylcyclohexene with chlorodimethylsilane ($n = 1$) occurs anomalously and involves double-bond migration to form a mixture of seven compounds: the *cis* and *trans* isomers of 2-, 3-, 4-chlorodimethyl(methylcyclohexyl)silanes and chlorodimethyl(cyclohexylmethyl)silane. Chlorodimethylsilane ($n = 2$) adds to 1-methylcyclohexene to form a mixture of the *cis* and *trans* isomers of dichloro(methyl)(2-methylcyclohexyl)silane and dichloro(cyclohexylmethyl)methylsilane. With trichlorosilane ($n = 3$), no other products than trichloro(cyclohexylmethyl)silane are formed. The hydrosilylation products were reacted with ethynylmagnesium bromide to synthesize the corresponding ethynyl derivatives.

Hydrosilylation of cycloalkenes and alkylidene-cycloalkenes has poorly been studied [1–5]. It is known that cyclopentene and 1-methylcyclopentene react with hydrosilanes to form respectively chloro(cyclopentyl)methyl- and chloro(cyclopentylmethyl)methylsilanes, which were then converted into ethynyl derivatives [6, 7].

Petrov *et al.* [8] showed that dichloro(methyl)silane adds to cyclohexene in the presence of platinum on carbon (0.5%) at 220°C to form dichloro(cyclohexyl)methylsilane in a low (6%) yield [8]. The nickel complex catalyst $\text{Ni}(\text{PPhMe}_2)\text{Cl}_2$ is more active: Dichloro(methyl)silane adds to cyclohexene (120°C, 20 h) to give a mixture of dichloro(cyclohexyl)methylsilane (34%) and chloro(cyclohexyl)methylsilane (41%) [9]. The addition of dichloro(methyl)silane to 1-methylcyclohexene in the presence of H_2PtCl_6 gives rise to chloro(cyclohexylmethyl)methylsilane [10]. The reactions of trichlorosilane with 1- or 3-methylcyclohexene provide trichloro(cyclohexylmethyl)silane [11].

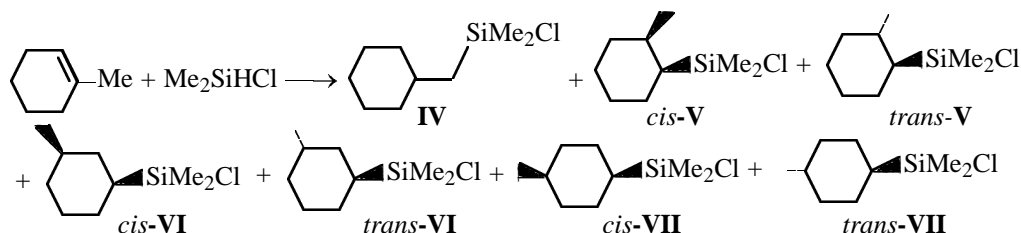
We performed a systematic study of hydrosilylation of cyclohexene, 1-methylcyclohexene, and isopropylidenecyclohexane with chlorodimethyl-, di-

chloro(methyl)-, and trichlorosilanes of the general formula $\text{Me}_{3-n}\text{SiHCl}_n$ ($n = 1-3$) in the presence of H_2PtCl_6 . The reaction occurs at 180°C. The yields of hydrosilylation products are 15–30, 40–50, and 45–60%, respectively. The reactions of cyclohexene with $\text{Me}_{3-n}\text{SiHCl}_n$ at all n afford chloro(cyclohexyl)methylsilanes.



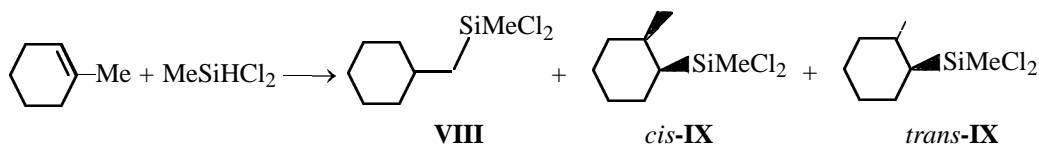
$n = 1$ (**I**), 2 (**II**), 3 (**III**).

1-Methylcyclohexene is hydrosilylated regio- and stereoselectively. The structures of the adducts are determined by the number of chlorine atoms (n) in the hydrosilylating agent. Thus chlorodimethylsilane forms a mixture of seven hydrosilylation products: chloro(cyclohexylmethyl)dimethylsilane (**IV**), *cis*- and *trans*-chloro(2-methylcyclohexyl)dimethylsilane (**V**), *cis*- and *trans*-chloro(3-methylcyclohexyl)dimethylsilane (**VI**), and *cis*- and *trans*-chloro(4-methylcyclohexyl)dimethylsilane (**VII**).

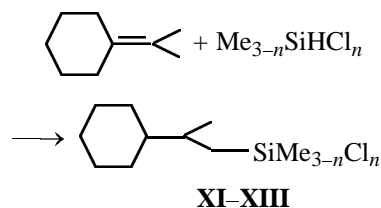
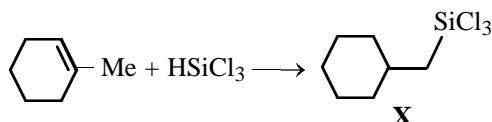


The reaction of dichloro(methyl)silane with 1-methylcyclohexene gave dichloro(cyclohexylme-

thyl)methylsilane (**VIII**) and *cis*- and *trans*- dichloro-(2-methylcyclohexyl)methylsilanes (**IX**).

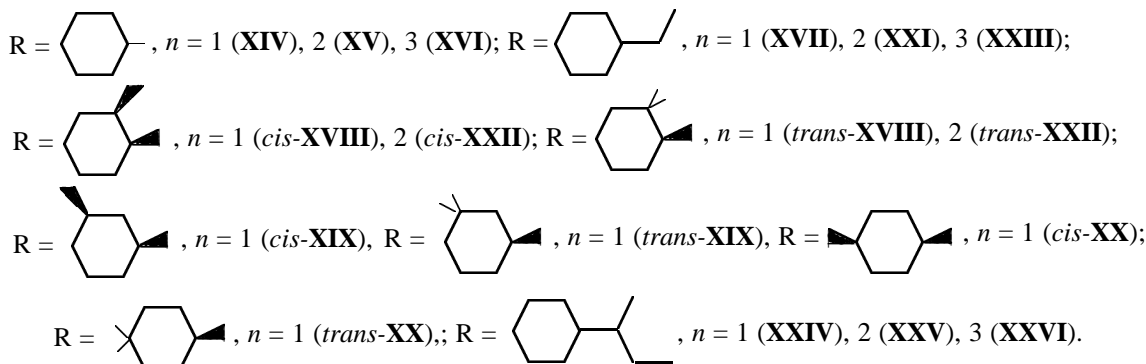
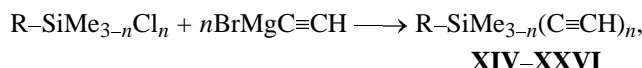


Trichlorosilane reacts with 1-methylcyclohexene to form exclusively trichloro(cyclohexylmethyl)silane (**X**), yield 60%.



The reaction of isopropylidenecyclohexane with all the hydrosilylating agents gives chloro(2-cyclohexylpropyl)methylsilanes **XI-XIII**.

Compounds **I-XIII** were reacted with ethynyl-magnesium bromide in THF to synthesize ethynyl derivatives **XIV-XXVI**.



(Cyclohexylmethyl)triethynylsilane (**XXIII**) is a colorless substance (mp 66°C), and the other ethynyl derivatives **XIV-XXII** and **XIV-XXVI** are colorless liquids distillable in a vacuum and stable to handling. The yields and constants of hydrosilylation products **I-XIII** and their ethynyl derivatives **XIV-XXVI** are listed in Tables 1 and 2, respectively. The structures of compounds **XIV-XXVI** are established by ^1H , ^{13}C , and ^{29}Si spectroscopy (Table 3).

EXPERIMENTAL

The NMR spectra were recorded on a Bruker DPX-400 spectrometer (400 MHz) for 15% solutions in CDCl_3 , internal reference HMDS.

Trichloro(cyclohexylmethyl)silane (X). A mixture of 9.6 g of 1-methylcyclohexene, 13.55 g of trichlorosilane, and 0.02 ml of H_2PtCl_6 in 2-propanol was

Table 1. Yields and constants of chlorosilanes **I–XIII**

Comp. no.	Yield, %	bp, °C (<i>p</i> , mm Hg)	d_4^{20}	n_D^{20}
I	17	74 (10)	0.9853	1.4525
II	46	68 (2)	1.1344	1.4695
III	51	67 (1)	1.2469	1.4755
IV–VII	21	80 (4)	0.9721	1.4508
VIII, IX	51	83 (3)	1.0759	1.4735
X	60	85 (4)	1.1765	1.4755
XI	32	99 (1)	0.9528	1.4640
XII	41	110 (3)	1.0569	1.4740
XIII	46	115 (4)	1.1896	1.4775

heated (5 h at 120°C and 5 h at 180°C) in an ampule housed in an autoclave and then distilled in a vacuum. Yield 13.8 g (60%) (Table 1).

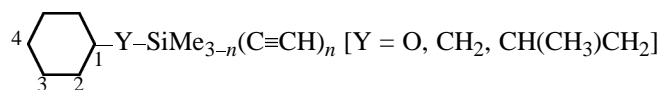
Compounds **I–IX** and **XI–XIII** were prepared in a similar way (Table 1).

(Cyclohexylmethyl)triethynylsilane (XXIII). To 11.6 g of compound **X** in 50 ml of ether we added dropwise with stirring ethynylmagnesium bromide prepared from 3.65 g of Mg, 16.5 g of EtBr, and cetylene in 120 ml of THF. After 30-min stirring, the mixture was decomposed with water and 5% HCl, subjected to usual workup, dried with CaCl₂, the solvents were removed at reduced pressure (water-jet vacuum), and the residue was sublimed in a vacuum

Table 2. Yields, constants, and elemental analyses of ethynylsilanes **XIV–XXVI**

Comp. no.	Yield, %	bp, °C (<i>p</i> , mm Hg)	d_4^{20}	n_D^{20}	Found, %			Formula	Calculated, %		
					C	H	Si		C	H	Si
XIV	67	83 (10)	0.8762	1.4550	71.73	10.68	17.20	C ₁₀ H ₁₈ Si	72.20	10.90	16.89
XV	65	80 (4)	0.9187	1.4760	74.15	9.33	16.01	C ₁₁ H ₁₆ Si	74.92	9.15	15.33
XVI	64	85 (1)	0.9310	1.4895	77.17	7.78	15.29	C ₁₂ H ₁₄ Si	77.34	7.57	15.08
XVII–XX	71	70 (10)	0.8846	1.4465	72.80	10.92	16.02	C ₁₁ H ₂₀ Si	73.25	11.18	15.57
XXI, XXII	66	55 (1)	0.9034	1.4730	75.78	9.54	14.59	C ₁₂ H ₁₈ Si	75.71	9.53	14.75
XXIII	63	66 ^a	—	—	78.16	8.00	13.99	C ₁₃ H ₁₆ Si	77.92	8.05	14.02
XXIV	67	95 (1)	0.8664	1.4645	74.97	11.72	13.79	C ₁₃ H ₂₄ Si	74.91	11.61	13.48
XXV	69	103 (1)	0.8958	1.4765	75.68	10.15	12.71	C ₁₄ H ₂₂ Si	76.98	10.15	12.86
XXVI	65	110 (1)	0.9245	1.4860	77.78	9.14	11.73	C ₁₅ H ₂₀ Si	78.88	8.82	12.30

^a Melting point.

Table 3. ¹H, ¹³C, and ²⁹Si NMR parameters of compounds **XIV–XXVI**

Comp. no.	¹ H NMR spectrum, δ, ppm				¹³ C NMR spectrum, δ _C , ppm				²⁹ Si NMR spectrum, δ _{Si} , ppm
	SiMe	R	≡CH		SiMe	R	≡CH	SiC≡	
XIV	0.07 s	0.63 m, 1.16 m, 1.69 m	2.29		−3.95	25.38 (C ¹), 26.76 (C ⁴), 27.02 (C ³), 27.81 (C ²)	93.64	88.56	−13.40
XV	0.28 s	0.80 m, 1.23 m, 1.76 m	2.41		−3.65	26.19 (C ¹), 26.31 (C ⁴), 26.79 (C ³), 27.76 (C ²)	95.19	84.96	−34.21
XVI	—	0.92 m, 1.28 m, 1.80 m	2.54		—	25.27 (C ¹), 26.22 (C ⁴), 26.69 (C ³), 27.52 (C ²)	96.24	81.63	−60.09
XVII–	0.07 s,	0.61 d (SiCH ₂), 0.86 d.d.d	2.29,		−0.88	22.68 (SiCH ₂), 26.21	92.03,	89.75,	−19.50, −19.24,

Table 3. (Contd.)

Comp. no.	¹ H NMR spectrum, δ , ppm			¹³ C NMR spectrum, δ_C , ppm				²⁹ Si NMR spectrum, δ_{Si} , ppm
	SiMe	R	\equiv CH	SiMe	R	\equiv CH	SiC \equiv	
XX	0.10 s, 0.12 s, 0.16 s	(4H _a), 0.96 q.t (4H _a), 1.04 d.t (3H _a), 1.18 d.t (4H _e), 1.28 m (3H _e)	2.30, 2.34, 2.35		(C ⁴), 26.48 (C ³), 35.48 (C ¹), 36.58 (C ²), 35.89 (C ¹), 37.74 (C ²)	93.26, 93.48, 93.69	89.85	–19.01, –17.47, –16.75, –16.48
XXI	0.35 s	0.75 d (SiCH ₂), 0.98 d.d.d (2.6H _a)	2.41	–0.66	23.14 (SiCH ₂), 26.25	94.89	86.11	–38.25
XXII	–	1.18 q.t (4H _a), 1.25 q.t (3.5H _a), 1.60 m (4H _e), 1.66 d.t (3.5H _e), 1.70 m (1H _a), 1.82 m (2.6H _e)	2.42, 2.43	–	(C ⁴), 26.49 (C ⁴), 26.68 (C ³), 26.84 (C ³), 33.86 (C ¹), 34.15 (C ¹), 35.15 (C ¹), 35.34 (C ²), 35.48 (C ²), 36.40 (C ²)	95.07, 96.24		–34.29, –33.89
XXIII	–	0.90 d (SiCH ₂), 1.04 d.d.d (2.6H _a), 1.65 q.t (4H _a), 1.27 q.t (3H _a), 1.63 m (4H _e), 1.67 m (1H _e), 1.71 m (3H _e), 1.86 d.q (2H _e)	2.55	–	23.93 (SiCH ₂), 25.96 (C ⁴), 26.19 (C ³), 33.67 (C ¹), 35.96 (C ²)	95.60	82.68	–63.97
XXIV	0.17 s	0.49 d.d [A part of the AB system of SiCH ₂ , ² J _{AB} 14.69, ³ J(H _A CCH) 9.72 Hz], 0.76 d.d [B part of the AB system of SiCH ₂ , ² J _{AB} 14.69, ³ J(H _B CCH) 4.3 Hz], 0.90 d (CH ₃ , J 6.8 Hz), 0.99 m (2H _a), 1.18 m (3H _a , CH, 1H _a), 1.62 m (4H _a , 4H _e , 3H _e), 1.72 d.t (2H _e)	2.34	–0.85	19.21 (CH ₃), 21.15 (SiCH ₂), 26.92 (C ⁴), 27.05 (C ³), 34.61 (C ¹) [30.36 (C ²), 28.81 (C ²)] (nonequiv.), 45.39 (CHCH ₃)	93.60	89.99	–15.74
XXV	0.34 s	0.63, 0.90 [SiCH ₂ , AB spectrum, ² J _{AB} 14.55, ³ J(H _A CCH) 9.78, ³ J(H _B CCH) 4.5 Hz], 0.95 d (CH ₃ CH), 0.99 m (2H _a), 1.3–0.98 (1H _a , 3H _a , 2H _a , CH), 1.79–1.56 (4H _a , 4H _e , 3H _e , 2H _e)	2.45	–0.86	18.92 (CH ₃), 20.69 (SiCH ₂), 26.74 (C ⁴), 26.89 (C ³), 34.38 (C ¹) [30.25 (C ²), 28.62 (C ²)] (nonequiv.) 44.99 (CHCH ₃)	94.84	86.06	–37.10
XXVI	–	0.77, 0.88 (SiCH ₂), 0.99 d (CH ₃ CH), 1.3–0.98 (1H _a , 3H _a , 2H _a , CH), 1.79–1.56 (4H _a , 4H _e , 3H _e , 2H _e)	2.55	–	18.74 (CH ₃), 20.80 (SiCH ₂), 26.63 (C ⁴), 26.83 (C ³), 34.14 (C ¹) [30.21 (C ²), 28.54 (C ²)] (nonequiv.), 44.74 (CHCH ₃)	95.87	82.79	–62.86

(1 mm Hg) on a boiling water bath to isolate 6.6 g (63%) of compound **XXIII** (Table 2).

Compounds **XIV–XXII** and **XXIV–XXVI** were prepared in a similar way (Table 2).

ACKNOWLEDGMENTS

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REFERENCES

1. Lukevits, E.Ya. and Voronkov, M.G., *Gidrosililirovanie, gidrogermilirovanie i gidrostannilirovanie* (Hydrosilylation, Hydrogermylation, and Hydrostannylation), Riga: Zinatne, 1964.
2. Lukevits, E.J. and Voronkov, M.G., in *Organic Insertion Reactions of Group IV Elements*, New York: Consultants Bureau, 1966.

3. Lukevits, E.J., Belyakova, Z.V., Pomerantseva, M.G., and Voronkov, M.G., in *Organometallic Chemistry Reviews*, Amsterdam: Elsevier, 1977.
4. Puhnarevich, V.B., Lukevits, E.Ya., Kopylova, L.I., and Voronkov, M.G., in *Perspektivy gidrosililirovaniya* (Perspectives of Hydrosilylation), Riga: Inst. Org. Soedin., Akad. Nauk LatvSSR, 1992.
5. Marciniak, E.B., *Comprehensive Handbook on Hydrosilylation*, Oxford: Pergamon, 1992.
6. Yarosh, O.G., Mirskov, R.G., Yarosh, N.K., Albanov, A.I., and Voronkov, M.G., *Zh. Obshch. Khim.*, 1999, vol. 69, no. 2, p. 251.
7. Yarosh, O.G., Zhilitskaya, L.V., Yarosh, N.K., Albanov, A.I., Burnashova, T.D., and Voronkov, M.G., *Zh. Obshch. Khim.*, 1999, vol. 69, no. 9, p. 1450.
8. Petrov, A.D., Ponomarenko, N.A., Sokolov, B.A., and Odabashyan, G.V., *Izv. Akad. Nauk SSSR, Otd. Khim. Nauk*, 1957, no. 10, p. 1206.
9. Kiso, Y., Kumada, M., Tamao, K., and Umeno, M., *J. Organomet. Chem.*, 1973, vol. 50, no. 1, p. 297.
10. Saam, J. and Speier, I.L., *J. Am. Chem. Soc.*, 1961, vol. 83, no. 6, p. 1361.
11. Selin, T.G. and West, R., *J. Am. Chem. Soc.*, 1962, vol. 84, no. 10, p. 1863.